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PPLICATION NO. FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/605,699 10/21/2003	Kiran V. Chatty	BUR920030120US1	2698
30678 7590 06/14/200	5	EXAMINER	
CONNOLLY BOVE LODGE &	Ł HUTZ LLP	VU, DAVID	
SUITE 800 1990 M STREET NW		ART UNIT	PAPER NUMBER
WASHINGTON, DC 20036-342	5	2818	

DATE MAILED: 06/14/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

			UK
	Application No.	Applicant(s)	
	10/605,699	CHATTY ET AL.	
Office Action Summary	Examiner	Art Unit	
	DAVID VU	2818	
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet v	vith the correspondence address	
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION.  Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication.  If the period for reply specified above is less than thirty (30) days, a rep If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailine earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a sly within the statutory minimum of th will apply and will expire SIX (6) MO e. cause the application to become A	reply be timely filed  rty (30) days will be considered timely.  NTHS from the mailing date of this communic  BANDONED (35 U.S.C. § 133).	cation.
Status			
<ul> <li>1) ⊠ Responsive to communication(s) filed on 22 A</li> <li>2a) ☐ This action is FINAL. 2b) ☒ Thi</li> <li>3) ☐ Since this application is in condition for allowated in accordance with the practice under</li> </ul>	s action is non-final. ance except for formal ma		ts is
Disposition of Claims			
4) ☐ Claim(s) 1-51 is/are pending in the application 4a) Of the above claim(s) 32-51 is/are withdra 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-31 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) 1-51 are subject to restriction and/or	wn from consideration.		
Application Papers			
9) The specification is objected to by the Examina 10) The drawing(s) filed on 21 October 2003 is/are Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	e: a) ☐ accepted or b) ☒ e drawing(s) be held in abeya ction is required if the drawin	ince.  See 37 CFR 1.85(a). g(s) is objected to. See 37 CFR 1.1	
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreig  a) All b) Some * c) None of:  1. Certified copies of the priority documer  2. Certified copies of the priority documer  3. Copies of the certified copies of the priority documer  application from the International Burea  * See the attached detailed Office action for a list	nts have been received.  Its have been received in ority documents have bee au (PCT Rule 17.2(a)).	Application No n received in this National Stage	Э
Attachment(s)  1) Notice of References Cited (PTO-892)		Summary (PTO-413)	
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date 10/21/03; 12/24/03 08/10/04	, , , , , , , , , , , , , , , , , , ,	(s)/Mail Date Informal Patent Application (PTO-152) 	

### **DETAILED ACTION**

#### **Election/Restrictions**

1. Applicant's election without traverse of Group I (Claims 1-31) on 04/22/2005 is acknowledged.

Claims 32-51 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim.

Election was made without traverse in the reply filed on 04/22/2005.

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1-10 and 15-31 are rejected under 35 U. S. C. 102(b) as being anticipated by Kim et al. (US Pat. 5,675,170).

Regarding claims 1 and 22, Kim discloses, in figs. 3 and 4, a method of forming a semiconductor structure having improved latch-up robustness, the method comprising the steps of providing a substrate 1 including an injection site (I/O) and a plurality of circuit structures (NMOS/PMOS), wherein at least one of circuit structures has a susceptibility to a latch-up

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condition (col. 3, lines 8-16); and forming a plurality of contact regions (22/23/41/32/33/2/3/4) inter-spaced a varying distance between circuit structures.

Regarding claims 2, 3, 23 and 24, Kim discloses the distance varies with the proximity of contact regions to injection site; wherein distance varies with the susceptibility of circuit structures to a latch-up condition (figs. 3-4 and col. 3, lines 8-16).

Regarding claims 4-6 and 25-27, Kim discloses the plurality of contact regions comprises a first contact region 22 and a second contact region 23 spaced a first distance apart, and second contact region 23 and a third contact region 41 spaced a second distance apart different from first distance (figs. 3-4).

Regarding claim 7, Kim discloses the substrate comprises a well region having formed therein latch-up susceptible circuit structure (figs. 3-4).

Regarding claim 8, Kim discloses the well region (3/4) is n-type (figs. 3-4).

Regarding claim 9, Kim discloses the n-type well region (3/4) includes at least one contact comprising an n+ region (41/34) (figs. 3-4).

Regarding claim 10, Kim discloses at least one contact is coupled to Vdd (figs. 3-4).

Regarding claim 15, Kim discloses the plurality of contact regions are located along an axis and arranged vertically relative to axis (fig. 3).

Regarding claim 16, Kim discloses the plurality of contact regions are located along an axis and arranged horizontally relative to axis (fig. 3).

Regarding claim 17, Kim discloses the plurality of contact regions are located along an axis and arranged concentrically relative to axis (fig. 3).

Regarding claims 20 and 30, Kim discloses the distance increases as the distance of plurality of contact regions from injection site increases (figs. 3 and 4).

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Regarding claims 21 and 31, Kim discloses the plurality of contact regions are located along an axis so that spacing between adjacent contact regions increases as the distance from injection site increases (figs. 3 and 4).

Regarding claims 18, 19, 28 and 29, the limitations "wherein said distance is determined such that ...." (claims 18 and 28) or "wherein said external current injector is a cable discharge ...." (claims 19 and 29) are merely functional/intended use limitations that do not structurally distinguish the claimed invention over the prior. A recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim. See In re Casey, 370 F.2d 576, 152 USPQ 235 (CCPA 1967) and In re Otto, 312 F.2d 937, 939, 136 USPQ 458, 459 (CCPA 1963).

3. Claims 1, 7 and 11-14 are rejected under 35 U. S. C. 102(b) as being anticipated by Magee (US Pat. 4,642,667).

Regarding claim 1, Magee discloses, in figs. 1 and 2, a method of forming a semiconductor structure having improved latch-up robustness, the method comprising the steps of: providing a substrate 11 including an injection site (I/O) and a plurality of circuit structures (CMOS), wherein at least one of circuit structures has a susceptibility to a latch-up condition

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(col. 1, line 62 through col. 2, line 53); and forming a plurality of contact regions (32/33/34/35/36) inter-spaced a varying distance between circuit structures.

Regarding claims 7 and 11, Magee discloses, in figs. 1 and 2, substrate comprises a p-well region having formed therein latch-up susceptible circuit structure.

Regarding claim 12, Magee discloses, in figs. 1 and 2, a p-type well region includes at least one contact comprising a p+ region.

Regarding claim 13, Magee discloses, in figs. 1 and 2, at least one contact is coupled to ground.

Regarding claim 14, Magee discloses, in figs. 1 and 2, at least one contact is coupled to Vss.

### Conclusion

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to David Vu whose telephone number is (571) 272-1798. The examiner can normally be reached on Monday-Friday from 8:00am to 5:00pm. If attempt to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on (571) 272-1787. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR, Status information for unpublished

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applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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David Vu

May 26, 2005.